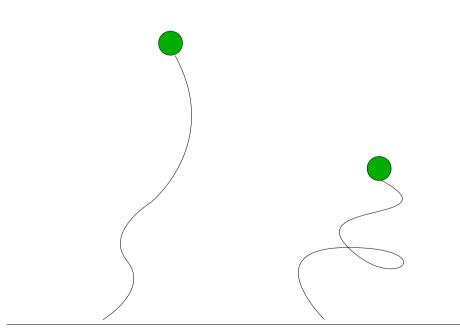
#### Presentation Phys 730 - Katia GASPERI

## Statistical study of single DNA molecules into dynamic array



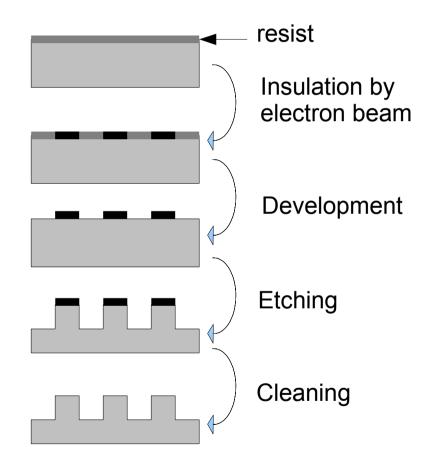
# Statistical study of single DNA molecules into dynamic array

- Research project lead by Laurence SALOME and Christophe VIEU (collaboration IPBS / Laas-CNRS, Toulouse, France)

- The project initially was expected to involved 4/5 teams.

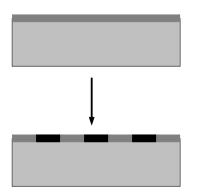
#### The project step by step Mold fabrication Stamp fabrication Contact printing Inking Video microscopy N N N N **DNA** fixation Image analysis

#### Mold fabrication



## Mold fabrication : EBL

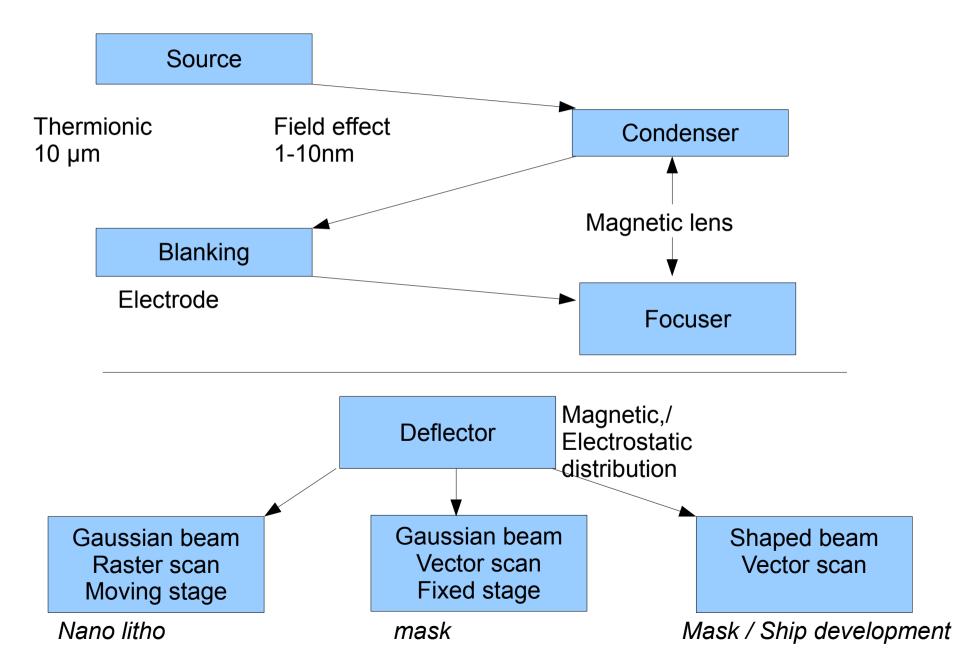
• EBL = Electron Beam Lithography



- Slow and expensive process
- High resolution

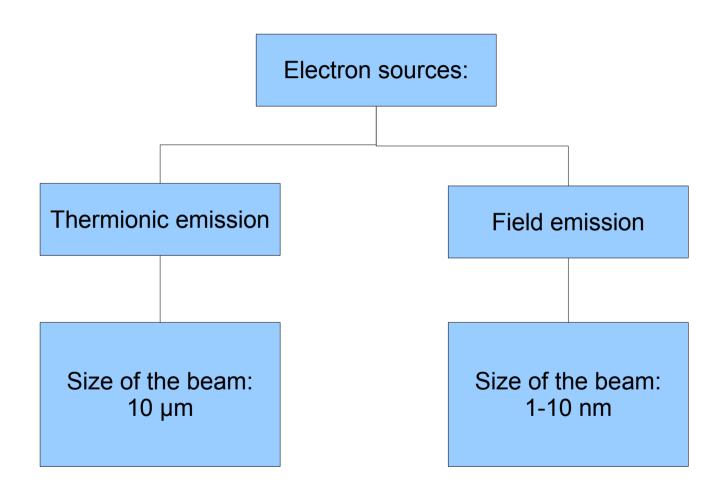


#### Mold fabrication : EBL

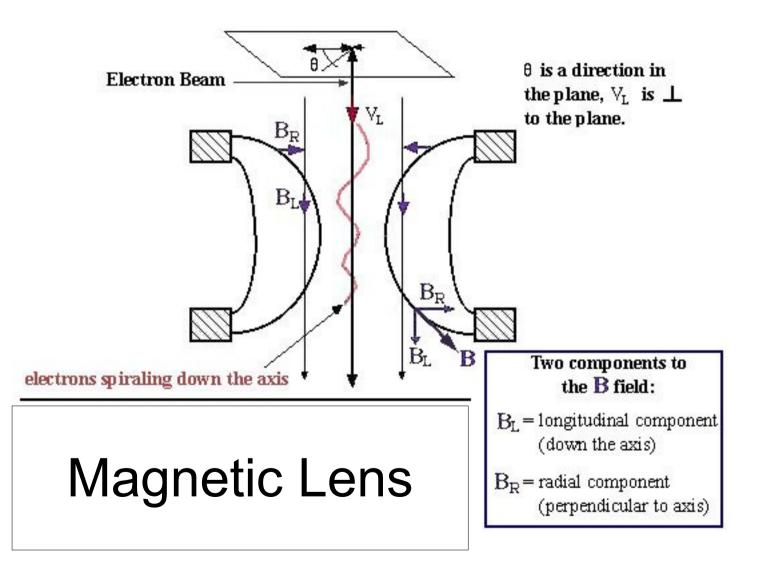


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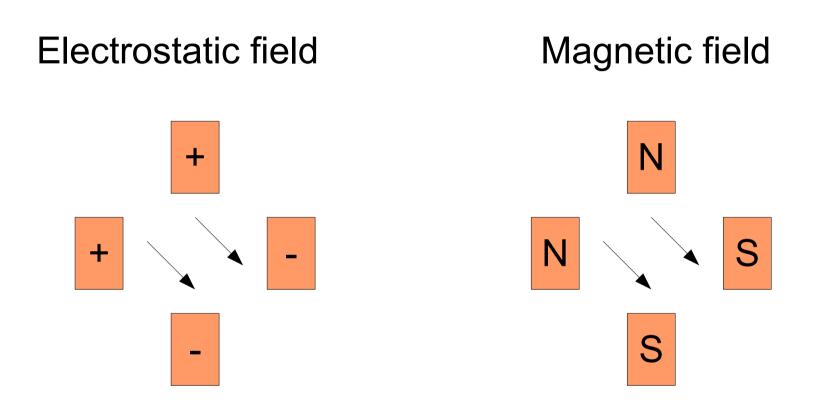
#### Mold fabrication : EBL Source

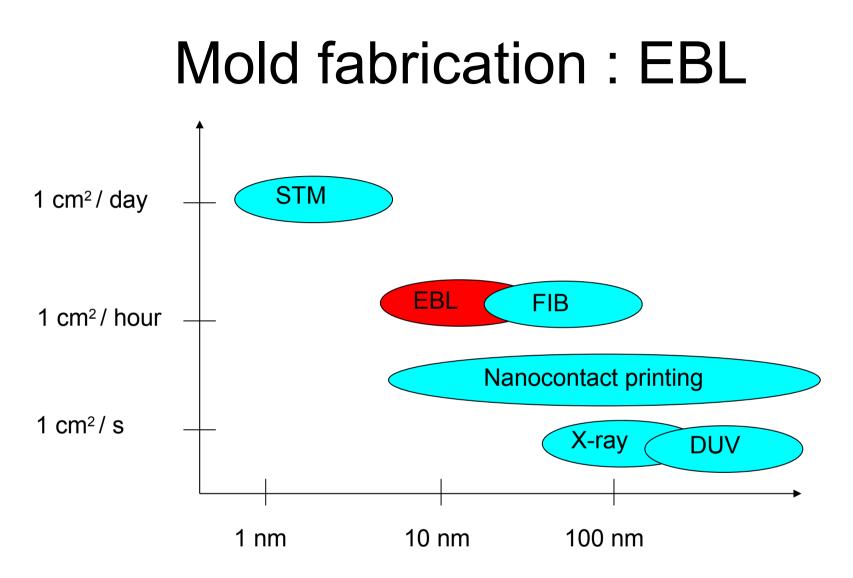


#### Mold fabrication : EBL



#### Mold fabrication : EBL Deflector





**STM = S**canning **T**unneling **M**icroscope

**EBL** = **E**lectron **B**eam Lithography

FIB = Focused Ion Beam

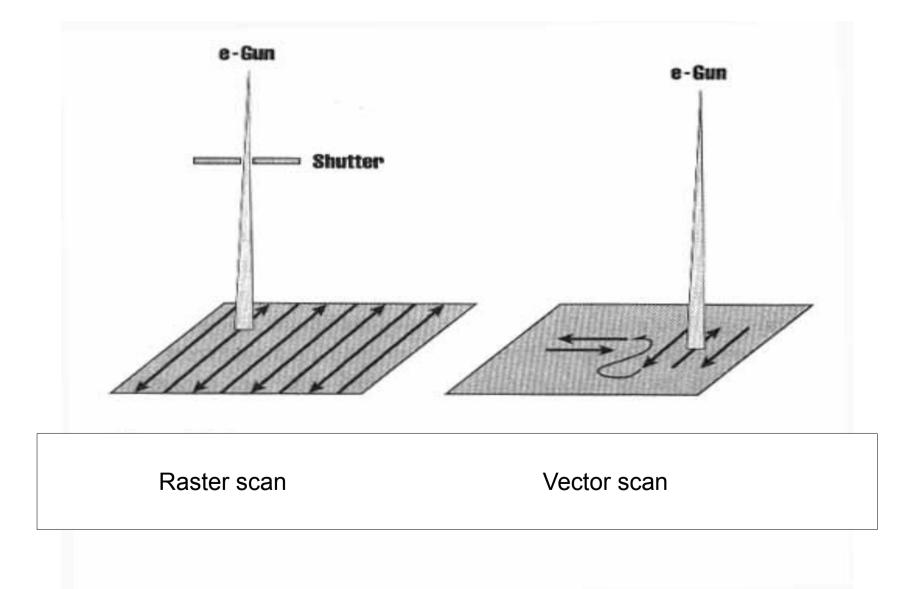
#### Mold fabrication : EBL Blanker

Role: turning the beam on and off

- pair of plates set up as a simple electrostatic deflector
- fast response time

To turn the beam off, a voltage is applied across the plates which sweeps the beam off axis until it is intercepted by a downstream aperture.

#### Mold fabrication : EBL Scanning methodologies

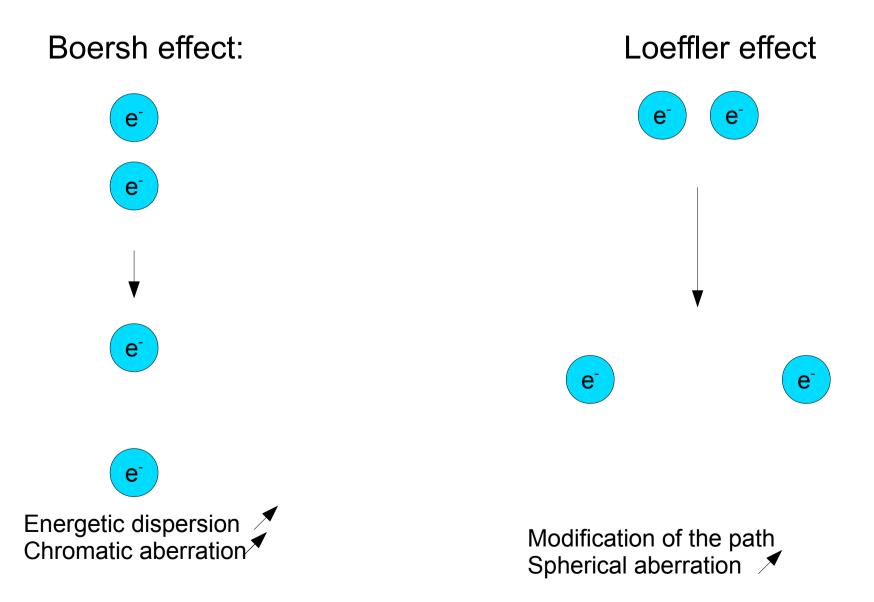


#### Mold fabrication : EBL Aberrations

$$d = \sqrt{d_g^2 + d_s^2 + d_c^2 + d_d^2}$$

- $d_{_g}$  : size of the source / demagnification
- d<sub>s</sub>: spherical aberration
- d<sub>c</sub>: chromatic aberration
- $d_d$ : diffraction limit

# Mold fabrication :EBL and more aberrations...



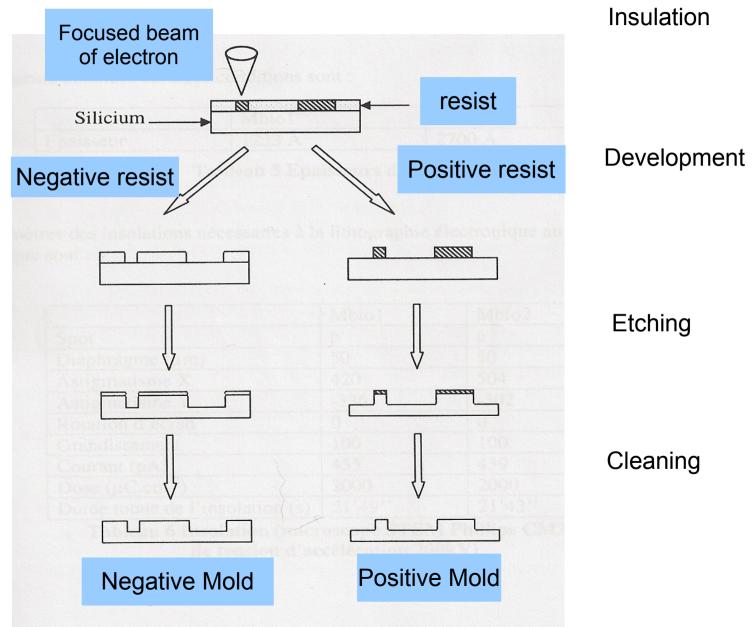
#### Mold fabrication : EBL Time

Dose = it/S

#### Example:

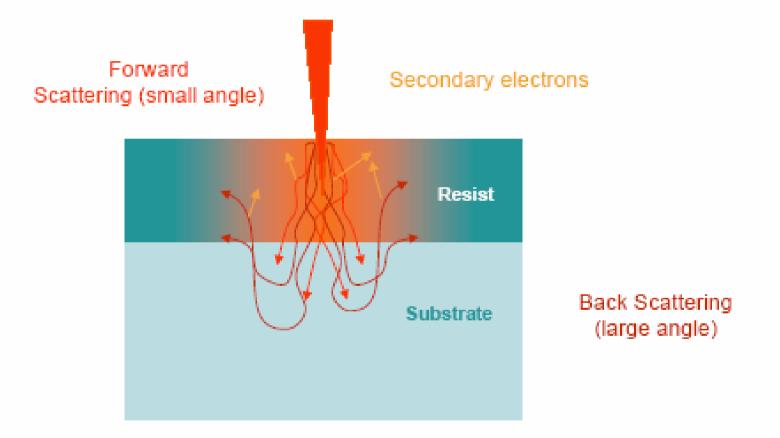
Current i= 450 pA Dose = 2000  $\mu$ C.cm<sup>-2</sup> Surface S = 2.8.10<sup>-4</sup> cm  $\rightarrow$  t = 23 minutes

## Mold fabrication: positive/negative resist



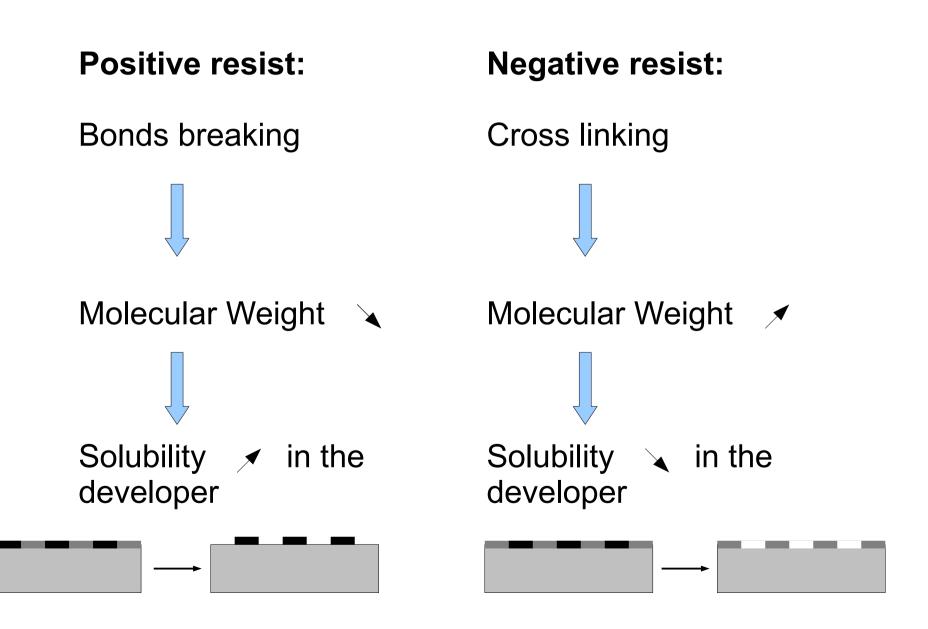
#### Mold fabrication : Resist

#### **Electron Scattering in Resist and Substrate**



#### The scattered electrons also expose the resist!

## Mold fabrication : Resist



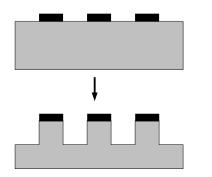
## Mold fabrication : RIE

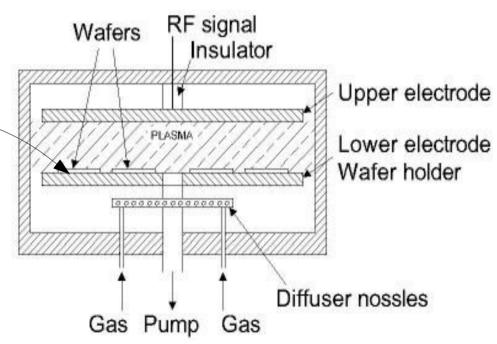
**RIE = R**eactive Ion Etching

#### - $U_0$ = bond energy of surface's atoms

- The neutral molecules of the plasma make U<sub>0</sub> decrease

- The ions accelerates when they are closed to the surface
- substrate = cathode
  - Interest: very anisotropic.





lon bombardement +

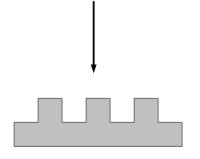
chemical reaction

Source: www.memsnet.org

## Mold fabrication: cleaning + SAM

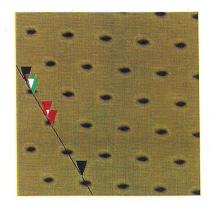
- Ultrasonic cleaning in acetone (remove the residues)
- Treatment anti-adherence

(Self auto-assembled molecule)



The mold is ready !

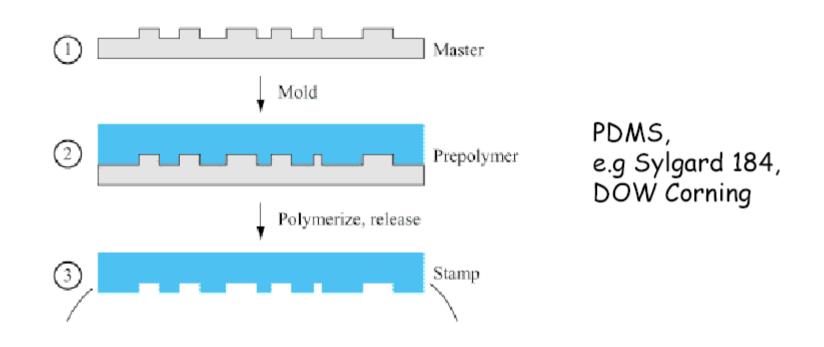
example:



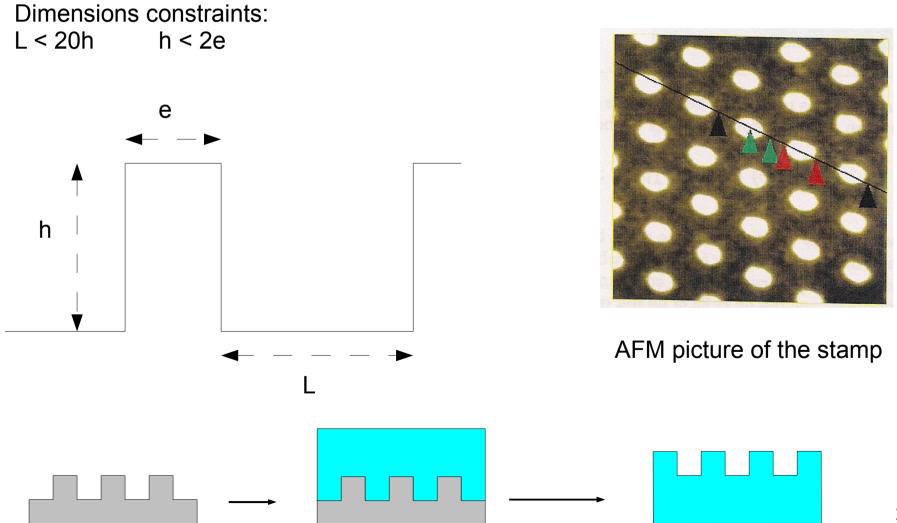
AFM picture of a mold Diameter of the holes : 200 nm Period of the array: 500 μm

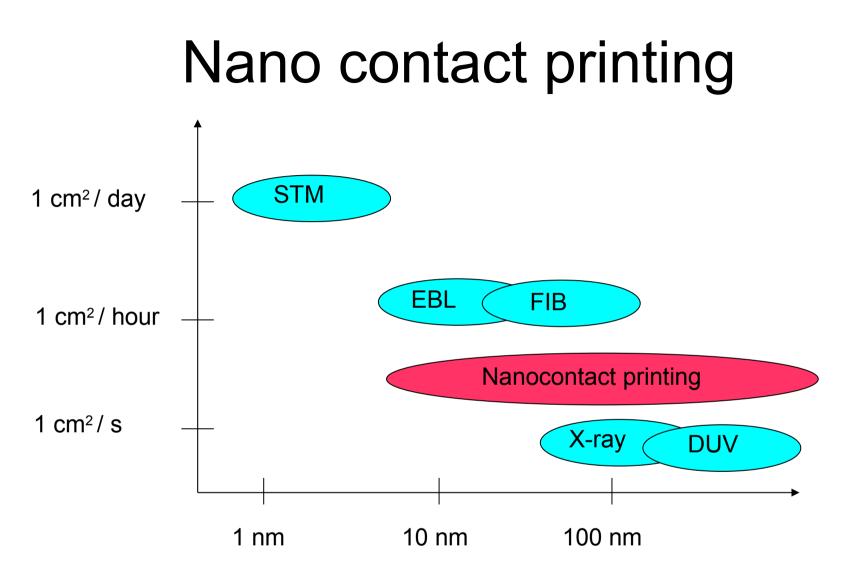
Resist: PMMA (Poly Methyl MethAcrylate) Developer: MIBK / IPA (1:3) and IPA (Methyl IsoButyl Ketone / IsoPropyl Alcool )

#### Stamp fabrication



#### Stamp fabrication





**STM = S**canning **T**unneling **M**icroscope

**EBL** = **E**lectron **B**eam Lithography

FIB = Focused Ion Beam

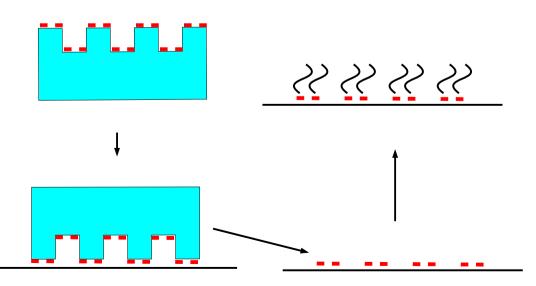
## Nano contact printing / DNA fixation

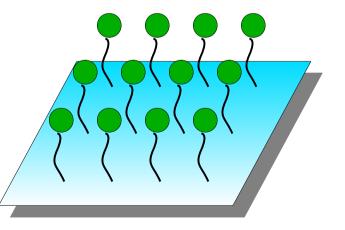
#### **Printing of biological molecules:**

- The **dilution** well selected lead to the possibility to make arrays of single molecules.

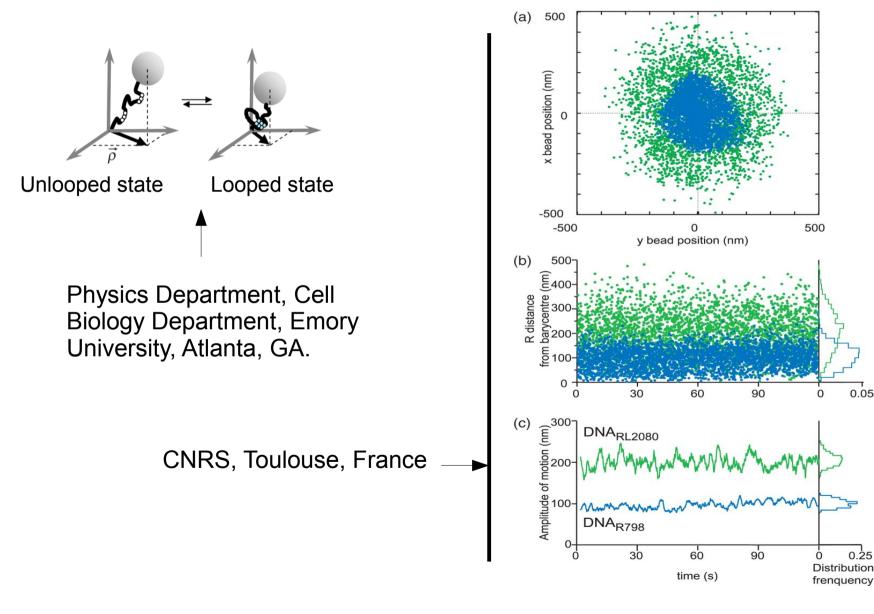
Important works: J.P. Renaud, A. Bernard,
A. Bietsch, B. Michel, H.R. Bosshard,
E. Delamarche, IBM Zurich.

Example of application: DNA 1. Functionalization of the surface = stamping of oligomers 2. Hybridization of DNA 3. Addition of biotine molecules





## Video microscopy / Image analysis



#### To conclude...

- Through this example, we can see that the nanotechnologies are a door open to multidisciplinary project
- Each technique improvement linked to this example is a step "forward" for other applications in various fields

#### References

"Nanostructuration microsensor", lecture, Christophe VIEU

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